

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination	
		10/553,470	LERNER, RALF	
Examiner		Art Unit		Page 1 of 1
Andrés López-Esquerra		2818		

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,515,826	02-2003	Hsiao et al.	360/126
*	B	US-6,242,320	06-2001	So, Sang Mun	438/406
*	C	US-6,156,621	12-2000	Nance et al.	438/406
*	D	US-6,514,858	02-2003	Hause et al.	438/640
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Hartmannsgruber, et al., "A Selective CMP Process for Stacked low-k/CVD Oxide Films", Microelectronic Enginerring, Vol. 50, pg. 53-58, 2000.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.